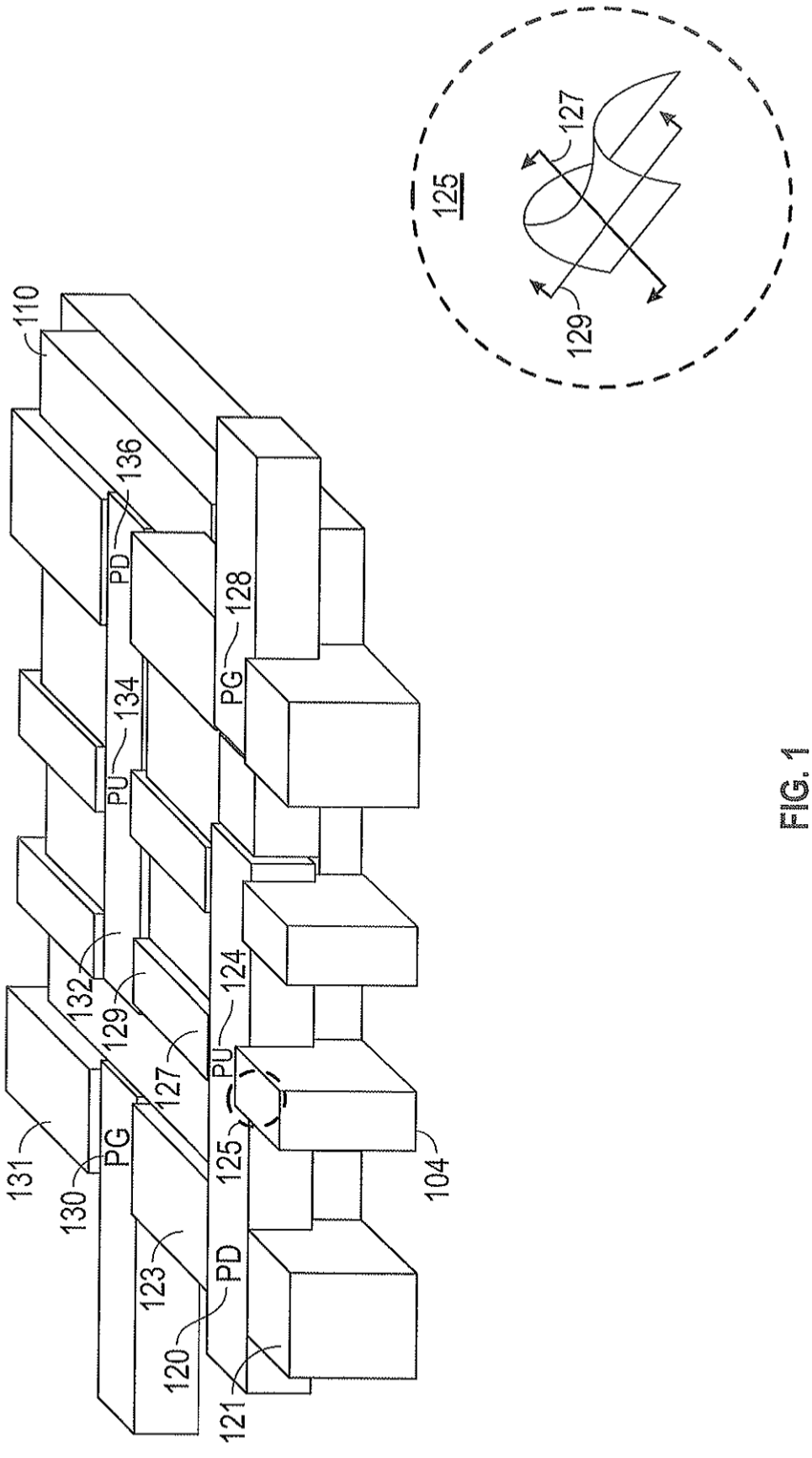

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121
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127
129

FIG. 1

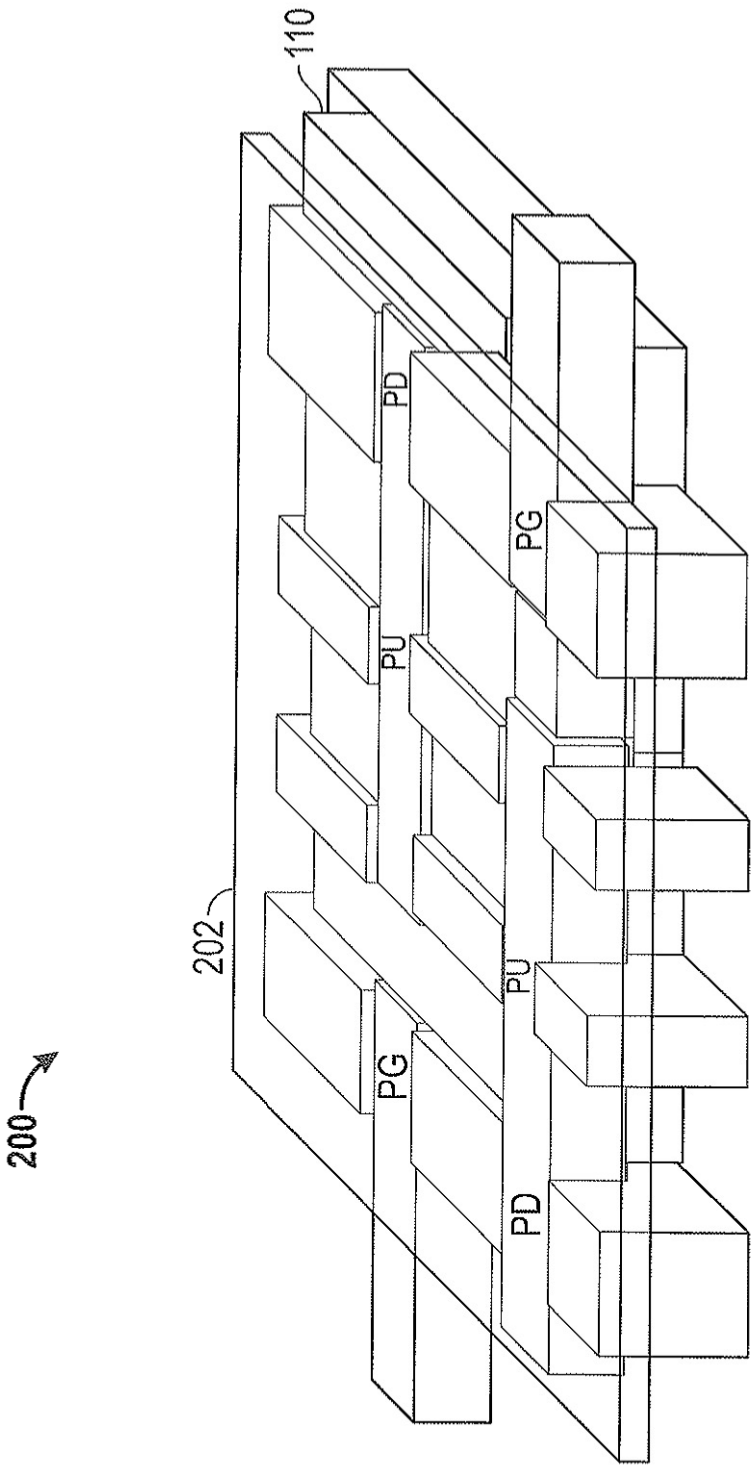


FIG. 2

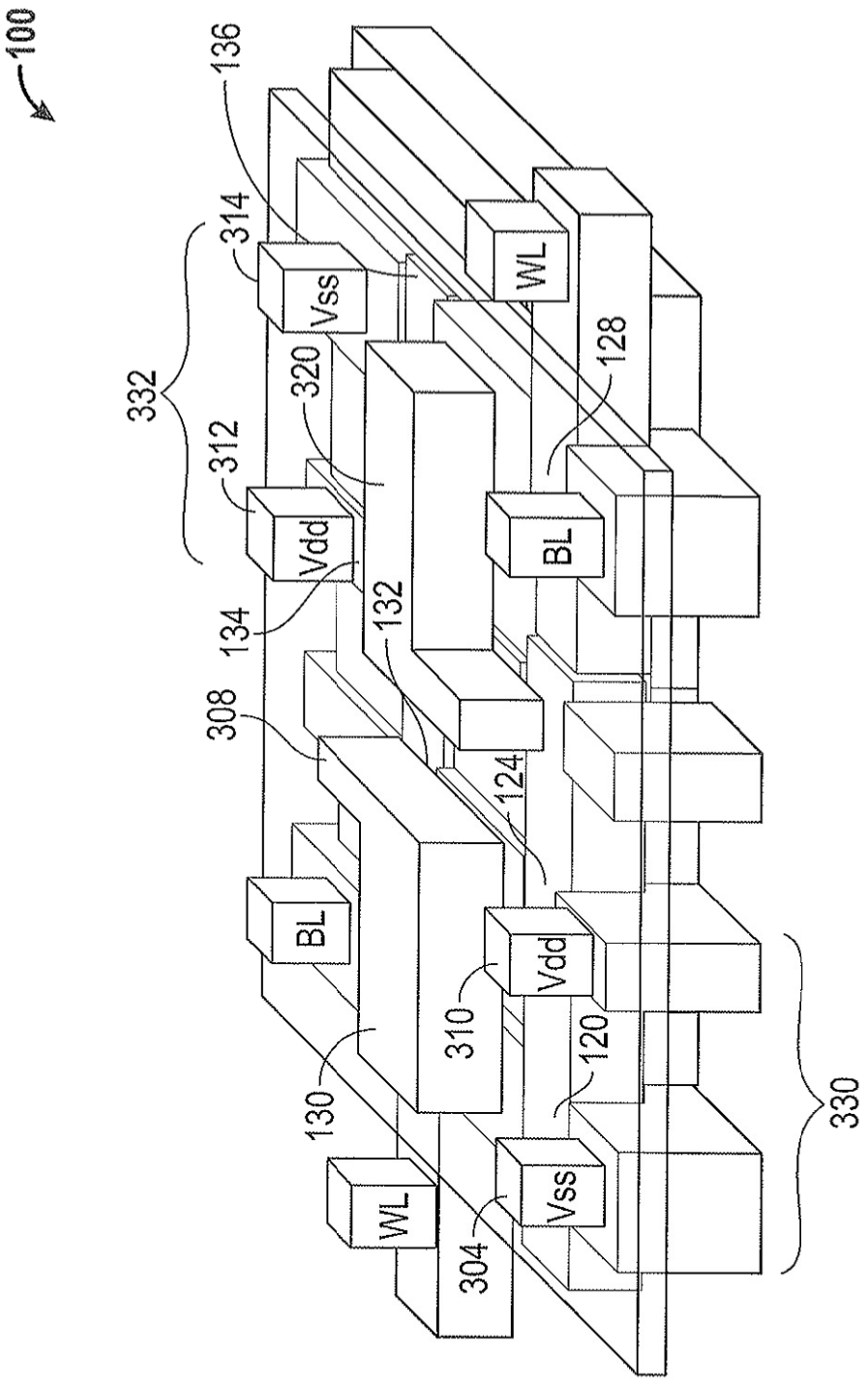

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314
Vss
WL
332
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312
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BL
134
132
308
124
BL
Vdd
310
120
130
330
WL
304
Vss

FIG. 3

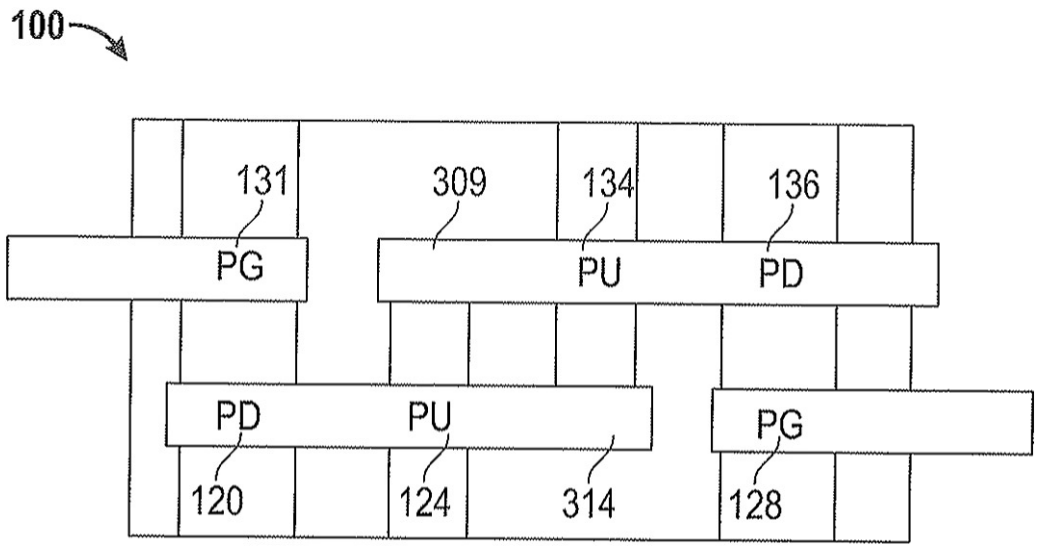

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309
134
136
PG
PU
PD
PD
PU
PG
120
124
314
128

FIG. 4

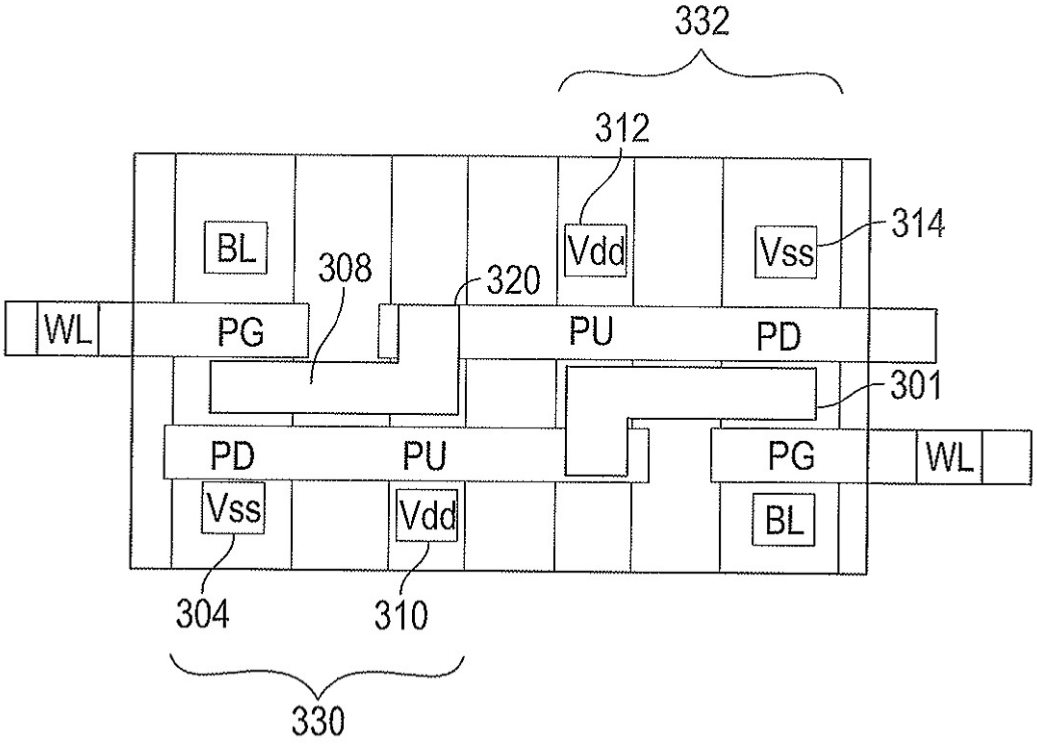

332
312
BL
308
320
Vdd
Vss
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WL
PG
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PD
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PD
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PG
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Vss
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BL
304
310
330

FIG. 5

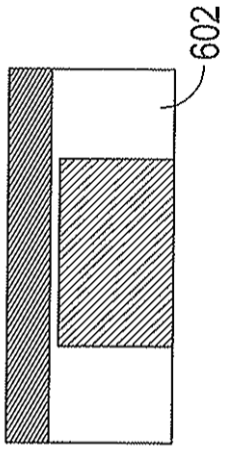


FIG. 7

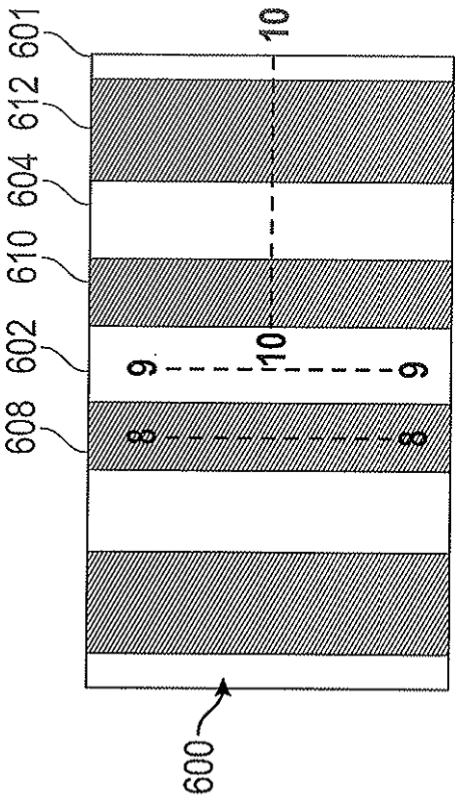


FIG. 6

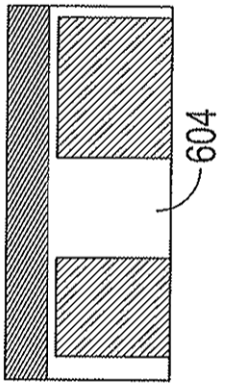


FIG. 10

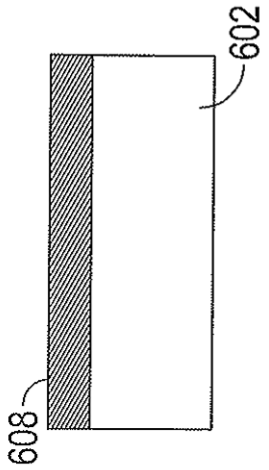


FIG. 9

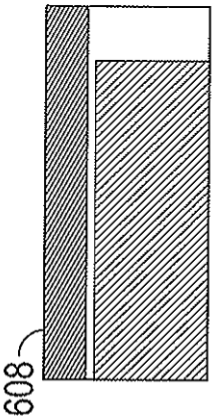


FIG. 8

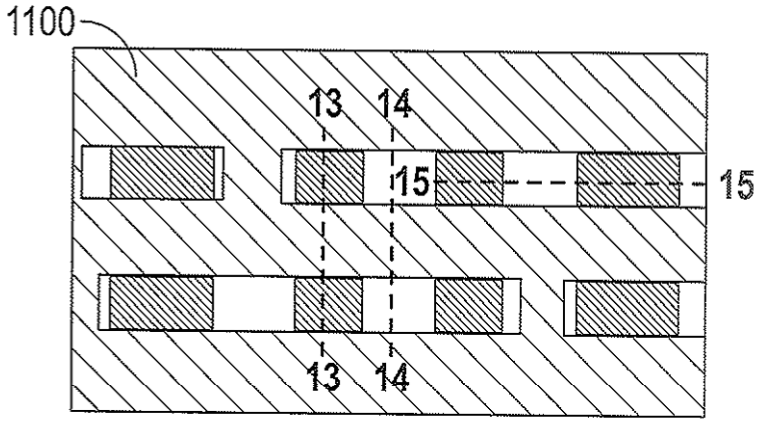


FIG. 11

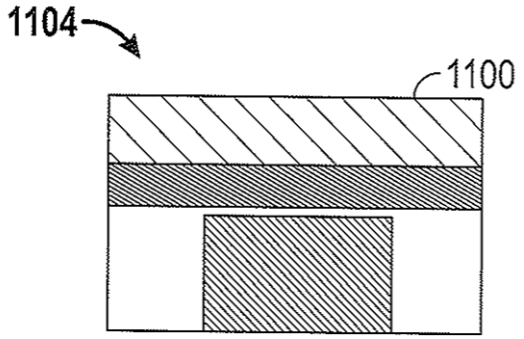


FIG. 12

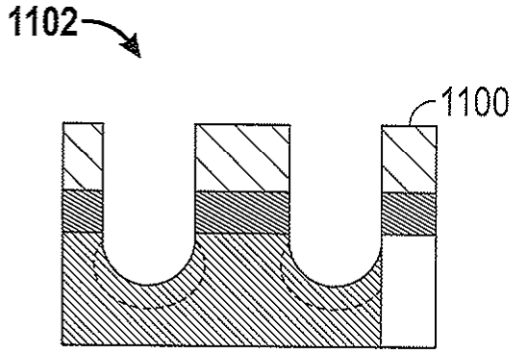


FIG. 13

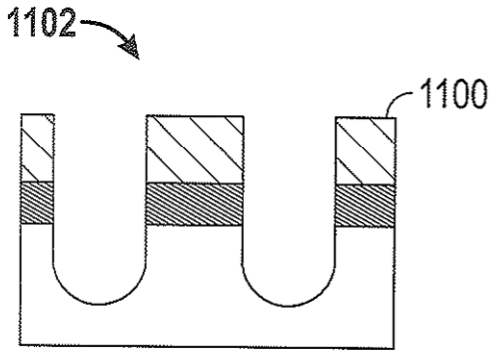


FIG. 14

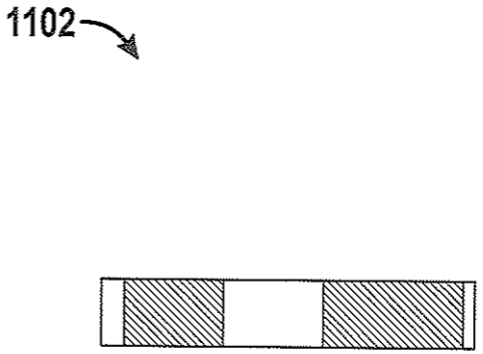


FIG. 15

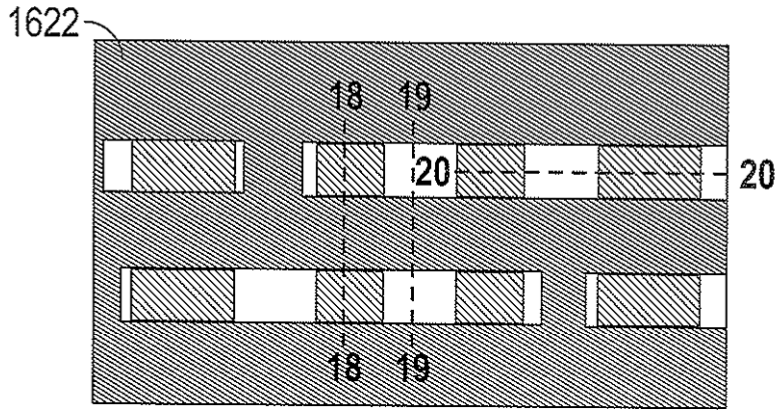


FIG. 16

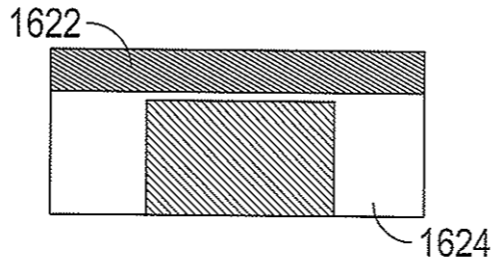


FIG. 17

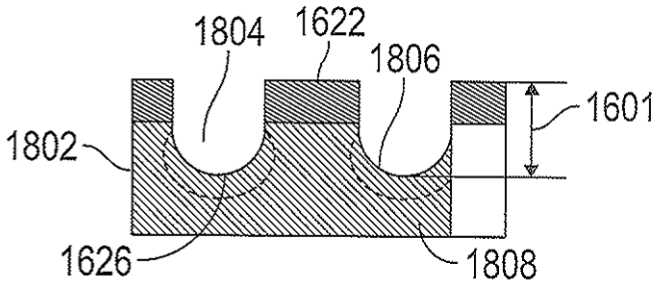


FIG. 18

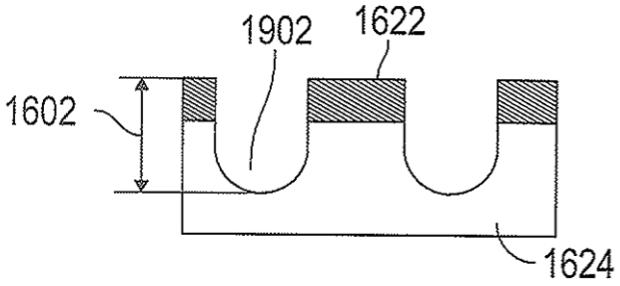


FIG. 19

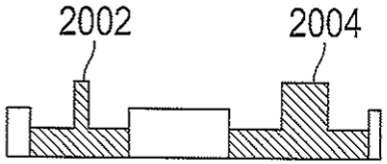


FIG. 20

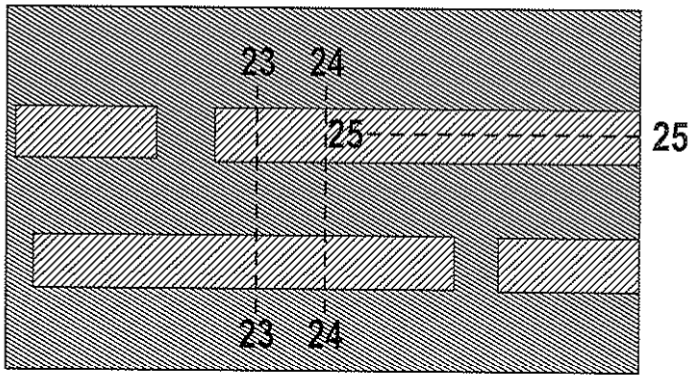


FIG. 21

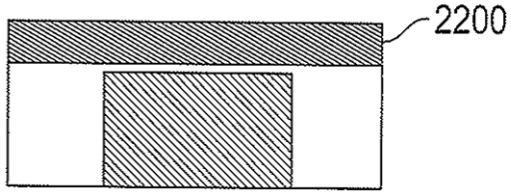


FIG. 22

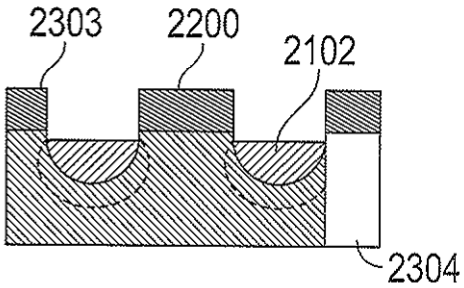


FIG. 23

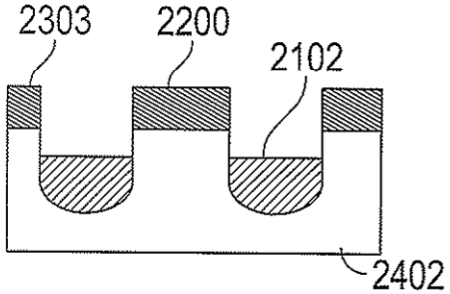


FIG. 24

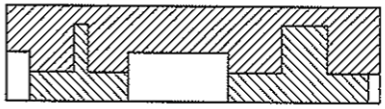


FIG. 25

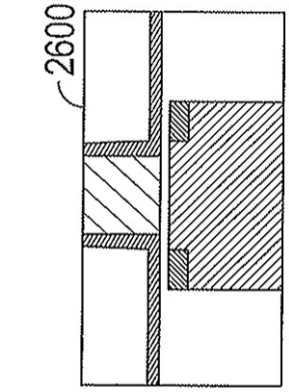


FIG. 27

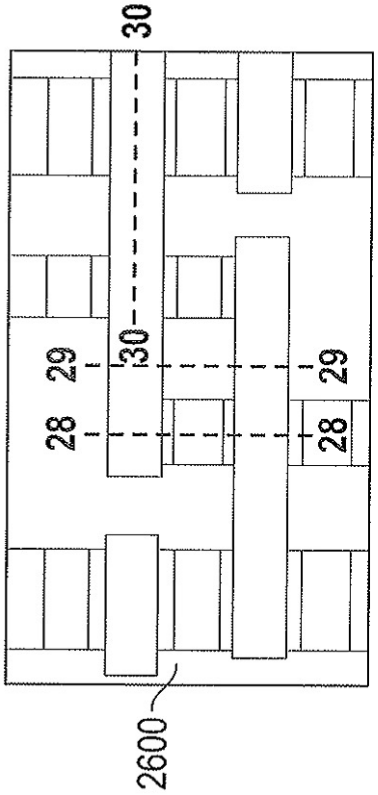


FIG. 26

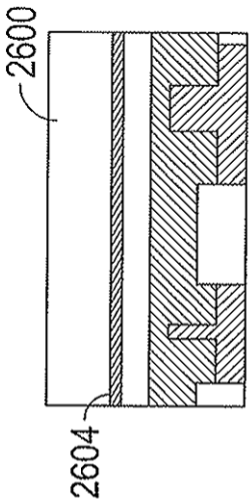


FIG. 30

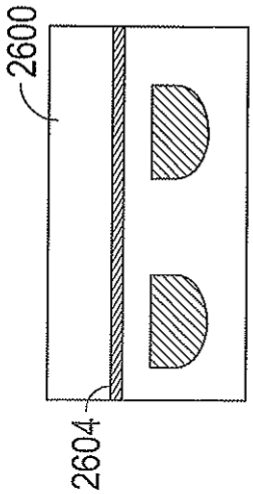


FIG. 29

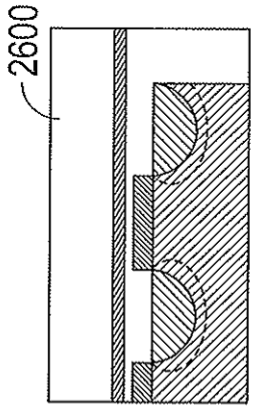


FIG. 28

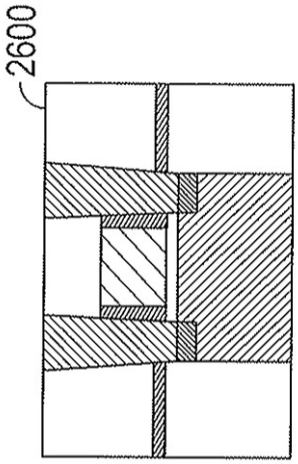


FIG. 32

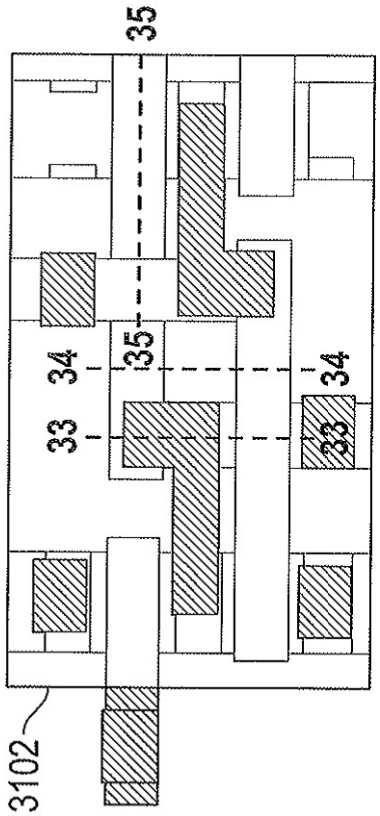


FIG. 31

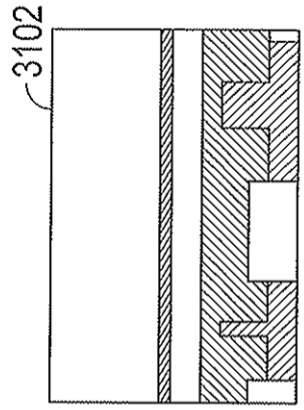


FIG. 35

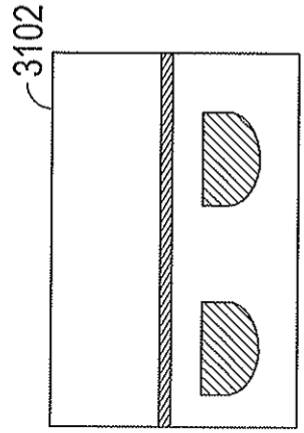


FIG. 34

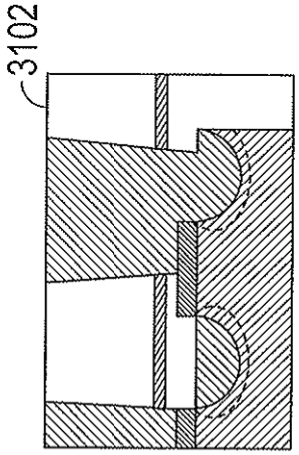


FIG. 33

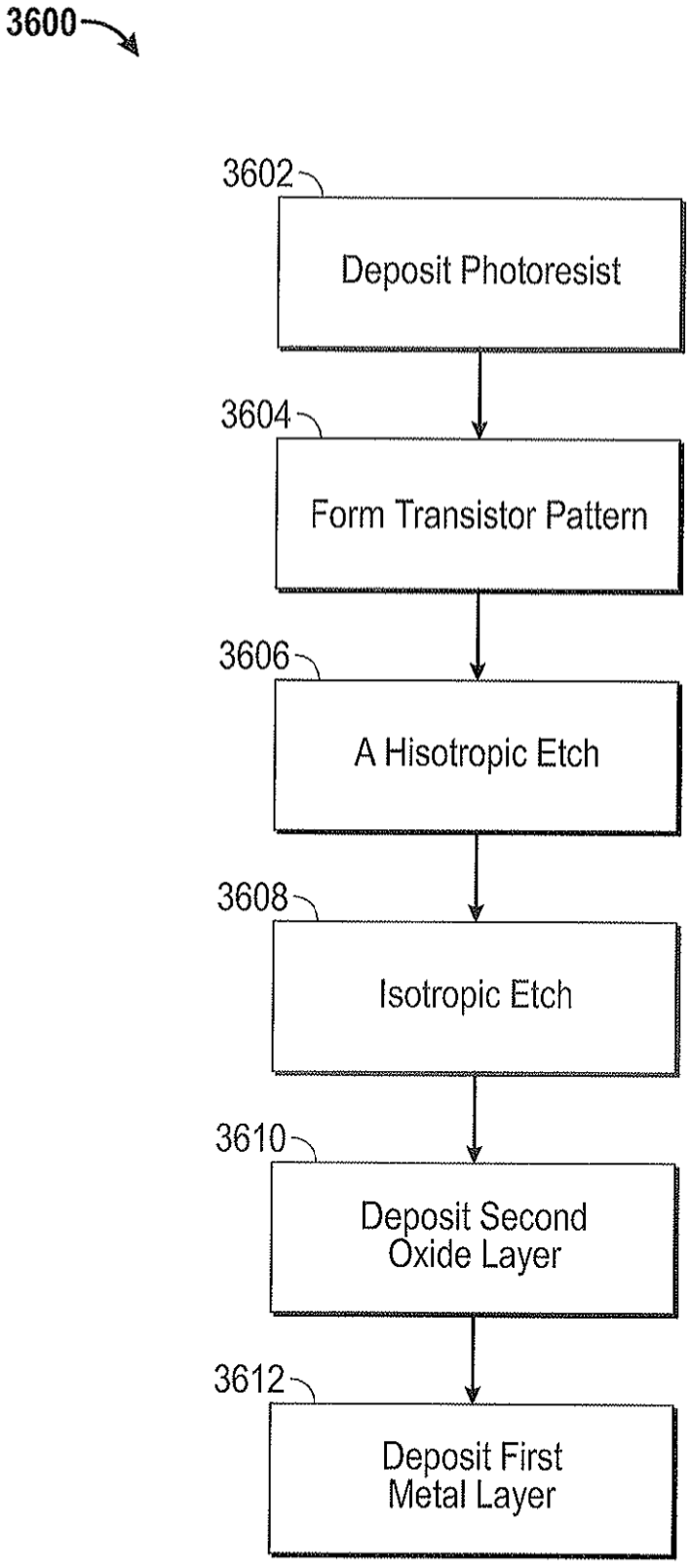

3600
3602
Deposit Photoresist
3604
Form Transistor Pattern
3606
A Hisotropic Etch
3608
Isotropic Etch
3610
Deposit Second Oxide Layer
3612
Deposit First Metal Layer

FIG. 36